

Advanced Films and Coatings Based on Atomic Layer Deposition

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Deadline for manuscript
submissions:

30 June 2023

Message from the Guest Editors

Dear Colleagues,

The advent of atomic and close-to-atomic-scale manufacturing has substantially improved the demand for depositing thin films free of defects and impurities for layered structures. Conventional thin-film processes face significant hurdles as the target film thickness reaches the atomic scale. As a result, atomic layer deposition (ALD) has emerged as a critical technique for depositing ultrathin films for a variety of applications, including, but not limited to, semiconductors, aerospace, renewable energy, optics, and biomedical applications.

This Special Issue is dedicated to research on the development and synthesis of new compounds and their application using the atomic layer deposition (ALD) technique. In this Special Issue, original research articles and reviews are welcome. Research areas may include (but are not limited to) the following:

- Atomic layer deposition (ALD)
- Plasma-enhanced atomic layer deposition (PALD)
- Atomic Layer Etching (ALE)
- Area-selective atomic layer deposition (AS-ALD)
- Surface modification
- 2D material deposition





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Message from the Editorial Board

Now more than ever, research is called for to produce technologies and improve knowledge to solve the major challenges faced by our society. The development of new materials and devices for (without the ambition to be exhaustive) energy, health and food technology, together with the need for establishing processes that reduce the impact on critical resources and the environment, is indeed at the center of most contemporary research. Surface science and engineering play a key role in this regard. Refining surfaces and their modifications provides new materials, architectures and processes with a huge potential to aid most societal challenges. *Coatings* is a well-established, peer-reviewed, online journal that focuses on the dissemination of publications in the field of surface science and engineering. *Coatings* publishes original research articles that report cutting-edge results and review papers on the hottest topics.

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